



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of)	Attorney Docket No.: TSUK0005
)	Confirmation No.: 5149
Tatsuo CHIBA et al.)	
)	Group Art Unit: 1756
Serial No.: 10/018,690)	
)	Examiner: Chacko-Davis, Daborah
Filed: December 20, 2001)	
)	
For: PHOTSENSITIVE ELEMENT,)	Date: January 19, 2005
PHOTSENSITIVE ELEMENT ROLL,)	
PROCESS FOR THE PREPARATION)	
OF RESIST PATTERN USING THE)	
SAME, RESIST PATTERN, RESIST)	
PATTERN LAMINATED)	
SUBSTRATE, PROCESS FOR THE)	
PREPARATION OF WIRING)	
PATTERN AND WIRING PATTERN)	

AMENDMENT (C)

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

In response to the non-final Office Action dated July 20, 2004, Applicants respectfully request reconsideration, under 37 C.F.R. § 1.111, of the application identified above as follows:

Amendments to the Claims are reflected in the listing of claims that begins on page 2 of this paper.

Remarks/Arguments begin on page 11 of this paper.